Atty. Docket No. OPP030889US Serial No: 10/676,645

Amendments to the Claims

Please cancel Claims 6-7, add new Claims 21-34, and amend the remaining Claims as shown below.

Listing of Claims

1. (Currently Amended) A semiconductor device having-a-pad-formed-by-exposing a-predetermined-region of a metal line formed-over-a-semiconductor-substrate, the-semiconductor device-comprising:

a via over a semiconductor substrate;

a barrier metal layer on a surface of the via;

a metal line in the via over the barrier metal layer; and

an alloy layer formed on an upper surface of the metal line-exposed-through-the pad, wherein the alloy layer is formed from a reaction-by-a-heat-treatment-at-a-contacting-surface between-comprises a metal of the metal line and a low melting point metal having a melting point less than or equal to 1000°C.

- 2. (Currently Amended) The semiconductor device of claim 1, wherein the metal line is made of comprises copper.
- 3. (Original) The semiconductor device of claim 1, wherein the metal having the melting point less than or equal to 1000°C is selected from the group consisting of aluminum, lead, and silver.
- 4. (Currently Amended) The semiconductor device of claim 1, wherein the a thickness of the alloy layer is less than a thickness of the metal line.

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- 5. (Currently Amended) The semiconductor device of claim 1, wherein a protection layer made of one of silicon nitride and or silicon oxynitride is formed on the metal line except where the a pad is formed.
 - 6. (Canceled)
 - 7. (Canceled)
- 8. (Currently Amended) The semiconductor device of claim [[6]]5, wherein a width of the pad is less than a width of the via.
 - 9-20. (Previously Canceled)
- 21. The semiconductor device of claim 1, wherein the pad is in a (New) predetermined region of the metal line.
- 22. (New) The semiconductor device of claim 21, wherein a width of the pad is less than a width of the via.
- 23. (New) The semiconductor device of claim 1, wherein the barrier metal comprises a metal selected from a group consisting of Ti, Ta, TiN, and TaN.
- 24. (New) The semiconductor device of claim 1, wherein the barrier metal has a thickness between 200 and 800 Å.
- 25. (New) The semiconductor device of claim 1, wherein the alloy comprises a reaction product of the metal line and the low melting point metal.

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- 26. (New) The semiconductor device of claim 1, further comprising an insulation layer over the semiconductor device, wherein the via is within the insulation layer.
- 27. (New) The semiconductor device of claim 26, wherein the insulation layer comprises an oxide layer.
- 28. (New) The semiconductor device of claim 23, wherein the barrier metal layer prevents the diffusion of copper from the metal line into the substrate.
- 29. (New) The semiconductor device of claim 1, wherein the alloy layer is completely within the via.
- 30. (New) The semiconductor device of claim I, wherein the barrier metal layer covers all surfaces of the via.
- 31. (New) The semiconductor device of claim 5, wherein the alloy layer is exposed through the pad.
- 32. (New) The semiconductor device of claim 1, wherein the barrier metal has a thickness of ~500 Å.
- 33. (New) The semiconductor device of claim 26, wherein a top surface of the alloy layer is lower than a top surface of the insulation layer.
- 34. (New) The semiconductor device of claim 1, wherein the barrier metal layer contacts the substrate.

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Amendments to the Figures

As requested by the Examiner during the interview of March 23, 2006, Figures 1A-1F have been amended to show a barrier metal layer 10 lining the surface of the via 100. Support for the barrier metal layer can be found in paragraphs [0006], [0008], [0010], and [0012] of the specification. Two Replacement Sheets (as required by 37 C.F.R. 1.121(d)) are attached to this Amendment.

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